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Bib Data Sheet

CONFIRMATION NO. 9165

SERIAL NUMBER 10/789,055	FILING DATE 02/27/2004 RULE	CLASS 430	GROUP ART UNIT 1752	ATTORNEY DOCKET NO. 30205/37328A
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## APPLICANTS

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## \*\* CONTINUING DATA \*\*\*\*\*

This application is a DIV of 09/878,803 06/11/2001 PAT 6,770,414

SJL

## \*\* FOREIGN APPLICATIONS \*\*\*\*\*

REPUBLIC OF KOREA 2000-32984 06/15/2000 SJL

## IF REQUIRED, FOREIGN FILING LICENSE GRANTED

\*\* 05/19/2004

Foreign Priority claimed <input checked="" type="checkbox"/> yes <input type="checkbox"/> no 35 USC 119 (a-d) conditions met <input checked="" type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> Met after Allowance Verifier and Acknowledged Examiner's Signature Initials	STATE OR COUNTRY KOREA, REPUBLIC OF	SHEETS DRAWING 2	TOTAL CLAIMS 12	INDEPENDENT CLAIMS 1
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## TITLE

Additive for photoresist composition for resist flow process

 All Fees